

Papers on Electron-Beam Lithography

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1. S.-Y. Lee, "Analytic Study of Apparent Resist Sensitivity in Electron-beam Lithography," *J. Vac. Sci. Technol.*, B43(6), 062602, November/December 2025.
2. S.-Y. Lee, "Effects of Lithographic and Pattern Parameters on Stability of Feature-Edge Location in Electron-beam Lithography," *J. Vac. Sci. Technol.*, B42(6), 062604, November/December 2024.
3. S.-Y. Lee, "Analytic Study of Exposure Contrast over Feature Edge in Electron-beam Lithography," *J. Vac. Sci. Technol.*, B41(6), 062606, November/December 2023.
4. S.-Y. Lee and M. N. Hasan, "Generalized Performance Optimization for Massively-Parallel Electron-beam Systems," *J. Vac. Sci. Technol.*, B41(4), 042603, July/August 2023.
5. M. N. Hasan, S.-Y. Lee, B.-S. Ahn, J. Choi and J.-S. Park, "Reduction of Exposing Time in Massively-Parallel Electron-beam Systems," *J. Vac. Sci. Technol.*, B40(3), 032602, May/June 2022.
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